

Supporting information

Electron-Selective Epitaxial/Amorphous Germanium Stack Contact for Organic-Crystalline Silicon Hybrid Solar Cells

Bingbing Chen¹, Jianhui Chen^{*1}, Kunpeng Ge¹, Linlin Yang¹, Yanjiao Shen¹,
Wanbing Lu¹, Li Guan¹, Lizhi Chu¹, Qingxun Zhao¹, Yinglong Wang¹, Ying Xu¹,
Yaohua Mai^{*2}

1 Hebei Key Lab of Optic-electronic Information and Materials, College of Physics
Science and Technology, Hebei University, Baoding 071002, China

2 Institute of New Energy Technology, College of Information Science and
Technology, Jinan University, Guangzhou, 510632, China

^{*1}E-mail: chenjianhui@hbu.edu.cn (Jianhui Chen); ^{*2}E-mail: yaohuamai@jnu.edu.cn
(Y. Mai)

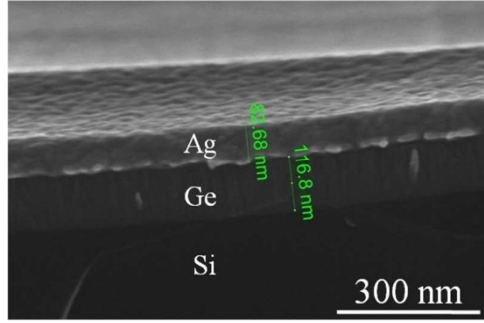


Figure S1 Cross-sectional SEM image of the Si/Ge/Ag heterostructure.

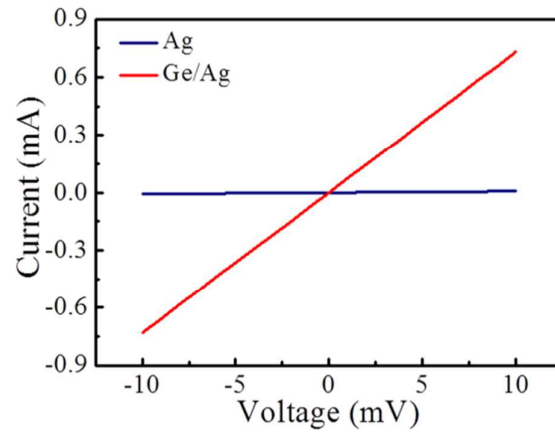


Figure S2 Current-voltage measurements between Ag fingers with and without the Ge thin layer.

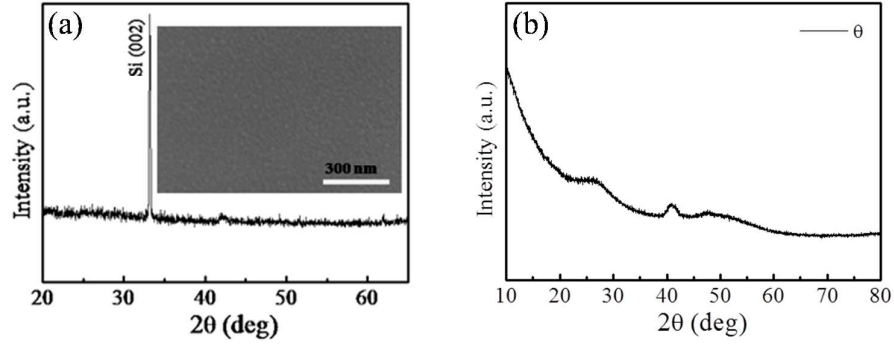


Figure S3 Different methods of X-ray diffraction pattern for Ge thin film on Si substrate. (a) is the general method, and (b) is the result using a small angle (2°) X-ray scattering. The peak of Ge is not observed by both methods, implying that the Ge film is amorphous. The inset in (a) is top-view SEM image of the a-Ge thin film on Si substrate, which shows the uniform and compact distribution for grains.

Table S-1 Carrier density and mobility of materials.

	Resistivity ($\Omega \cdot \text{cm}$)	Carrier density (cm^{-3})	Mobility ($\text{cm}^2 \cdot \text{V}^{-1} \cdot \text{s}^{-1}$)	
<i>a-Ge</i> (120 nm)	867	2.4×10^{12}	2982	This work
<i>c-Ge</i>	50	2.4×10^{13}	3900	Ref. [S1]
<i>n-Si</i>	0.1~10	$1 \times 10^{15} \sim 1 \times 10^{18}$	1500	Ref. [S1]
<i>Ag</i>	1.65×10^{-10}	-	-	Ref. [S2]

Reference

- [S1] Sze S. M. *Physics of Semiconductor Devices*, 2nd ed; Wiley Publications: New York, 1981.
- [S2] Matula R. A. Electrical Resistivity of Copper, Gold, Palladium, and Silver. *J. Phys. Chem. Ref. Data.* **1979**, 8, 1147-1298.